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Laser Materials Processing; and Micro/Nano Technologies

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Contents

vii	Authors
ix	Symposium Committees
xiii	Conference Committee
XV	Introduction
	VACUUM MANUFACTURING, OPTICAL THIN FILM AND SURFACE CHARACTERIZATION TESTING TECHNOLOGY
9295 02	Research on reverse association mechanism of the thermal control performance of conducting optical solar reflector and its antistatic properties [9295-102]
9295 03	Depth profile analysis of native oxide layer on GaAs (100) surface [9295-103]
9295 04	Theoretical and experimental analysis of optical gyroscopes based on fiber ring resonators [9295-104]
9295 05	Physical properties of ITO thin films prepared by ion-assisted electron beam evaporation [9295-105]
9295 06	Optical characteristics and damage thresholds of mirror in RLG dither [9295-106]
9295 07	The design and fabricate of wide angle 905nm narrow band filter [9295-108]
9295 08	Infrared transparent conductive films [9295-109]
9295 09	In-situ and real time stress of 30.4 nm Mo/Si multilayer mirror for the moon-based EUV Camera [9295-110]
9295 0A	High-reflectance of hybrid reflector with distributed Bragg reflector and metal mirror for flip-chip ultra-violet light-emitting diodes [9295-112]
9295 OB	Analysis of influence of wrinkled surface on scattering characteristics [9295-114]
	LASER MATERIALS PROCESSING AND MICRO-NANO FABRICATION
9295 OC	35CrMo steel surface by laser cladding Fe-based WC composite coating performance analysis [9295-202]
9295 0D	Improvement on ball-milling composite process of metal matrix micro-nanometer powder using nanosuspension as the precursor [9295-204]

9295 OE	The study of laser plasma plume radiation produced by laser ablation of silicon [9295-205]
9295 OF	Preparation and spectral properties of ${\rm Ho^{3+}/Tm^{3+}}$ co-doped Germanium glass active optical fiber material [9295-206]
9295 OH	Process of super-black shading material applied to the star sensor based on Ni-P alloys [9295-209]
9295 OI	Sub-wavelength surface structuring on stainless steel by femtosecond laser pulses [9295-210]
9295 OK	Temperature and thermal stress fields during the pulse train of long-pulse laser irradiating aluminium alloy plate [9295-216]
9295 OL	High repetition-rate and short pulse-width 1064nm laser in a composite crystal device [9295-217]
9295 OM	Research on the thermal effect of copper between adjacent pulses under moving laser irradiation [9295-218]
9295 ON	Numerical analysis of thermal effect in aluminum alloy by monopulse laser [9295-220]
9295 00	Thermal stress simulation of multi-pulse laser irradiate on fused silica [9295-221]
9295 OP	Numerical simulation for influence of pulse width on the temperature field of unidirectional carbon fiber [9295-226]
9295 OQ	Theoretical simulation of melt ejection during the laser drilling process on aluminum alloy by single pulsed laser [9295-227]
9295 OR	Investigation on the defect structure and optical damage resistance of In:Tm:LiNbO ₃ crystals with different doping concentrations of In ³⁺ [9295-229]
9295 OS	Analysis of thermodynamic effect in Si irradiated by pulsed-laser [9295-240]
9295 OT	Study and design of beam expander with wide aperture [9295-242]
9295 OU	Study on temperature distribution characteristics of alumina irradiating by irregular laser [9295-243]
9295 OV	Infrared thermography processing using Markov-PCA algorithm [9295-245]
9295 OW	Widely tunable mid-infrared optical parametric oscillator based on a multiple periods MgO:PPLN [9295-252]
9295 OX	Research of the optical structure for a handled laser-cleaner [9295-258]
9295 OY	Laser shock microforming of aluminum foil with fs laser [9295-259]
9295 07	The application of hand-held laser wire stripper in the field of gerospace [9295-260]

9295 10	Design and direct manufacture of non-assembly abacus by Selective Laser Melting [9295-304]
9295 11	Numerical analysis for search-based intra-cavity beam cleanup system [9295-307]
9295 12	Room temperature operation of 2.67 mJ pulse LD end pumped Q-switched Tm:YAG laser [9295-303]
9295 13	A novel method for fabricating curved frequency selective surface via 3D printing technology [9295-301]
	MICRO/NANO OPTICAL TECHNOLOGY AND APPLICATION
9295 14	Wavelength properties of DCG holograms under the conditions of different temperature and humidity [9295-311]
9295 15	The preparation and application of white graphene [9295-511]
9295 16	Three-peak standard white organic light-emitting devices for solid state lighting [9295-211]
9295 17	Non-isothermal molding technology research of ultra-precision glass lens [9295-611]
9295 18	Dynamic modulation of slow light by electro-optic effect in photonic crystal coupled resonator optical waveguide [9295-411]

Authors

Li, Zaijin, 07

Numbers in the index correspond to the last two digits of the six-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first four digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Cai, Ji-xing, 00, 0T Liang, Fengchao, 13 Lin, Haipeng, 01 Cao, Jian-lin, 09 Chang, Tianhai, 02 Liu, Fengdeng, 0H Liu, Jia, 0X Chen, Bo, 09 Chen, Chang, 03 Liu, Ruicheng, 10 Chen, Guibo, 0N Liu, WenJin, 11 Chen, ShanQiu, 11 Liu, Xiaoxi, OZ Chen, Xin-yu, 0W, 12 Liu, Yang, 10 Liu, Yao-ying, 04 Chen, Yong, 06 Cheng, Hongchang, 03 Liu, Yuiie, 14 Cheng, Man, 0D Ma, Yao, OP, OS Mao, Hongxia, OB Cheng, Xing, 03 Cui, Dan-feng, 04 Miao, Zhuang, 03 Cui, Xiao-wen, 04 Niu, Sen, 03 Ding, Quanxin, 14 Pan, Li, 0V Dong, LiZhi, 11 Qi, Litao, 01 Fan, Chuanhui, 0U Qin, Hengfeng, 0C Feng, Yayun, 0Y Qiu, Yang, 05 Gao, C. M., 0F Qu, Yi, 07 Gao, Jie, OR Shen, Qing, 0D Gao, Jinsong, 13 Shi, Baohua, 07 Gu, Xiu-ying, 0K, 0N, 0Q Shi, Feng, 03 Song, Changhui, 10 Guo, Kunping, 16 Guo, Ming, 00, 0Q, 0S, 0T Song, Xuedi, 12 Sun, Wei-guo, 08 Guo, Y. Y., 0F Han, K. X., 0F Tan, F., OF Tang, Qingju, 0V He, Fei, 09 He, Xing, 11 Tao, Bo, 17 He, ZheXi, 0X Tao, Fei, 08 Hu, Jinping, 01 Tong, Jianqiang, OR Hu, Yan, 11 Wan, Yong, 18 Hua, Xijun, 0Y Wang, Chao, 0W Hua, Yingun, OY Wang, Di, 0M, 0P, 0Q, 0U Huang, Huamao, 0A Wang, Di, 10 Huang, Qingju, 0E Wang, Hai-feng, 09 Huang, Zhen, OR Wang, Hong, 0A Jin, Guang-yong, OK, OL, OM, ON, OO, OP, OQ, OS, Wang, Hongyu, 0D OT, OU, OW, 12 Wang, J., 0F Jin, Yangli, 05 Wana, Jiaiia, 05 Li, Changhong, 18 Wang, Jiliang, 06 Li, Hongtao, OV Wang, Jilin, 0Z Wang, JunLong, 0X Li, Hongyu, 07 Li, Mingxin, ON, OQ, OS Wang, L. L., OF Li, Wengiang, 14 Wang, Li-wen, 08 Li, Xiangfeng, 0D Wang, Lei, 0V Li, Yan-na, 04 Wang, Long, 03 Li, Yinliang, 06 Wang, Xiao-dong, 09 Li, Yun-peng, 09 Wang, Xiao-duo, 09

Wang, Xuefeng, 0X

Wang, Yong-hua, 04

Wang, Zijian, OL

Wei, Bin, 16

Wei, Guang, 06

Wei, Li-ping, 04

Wei, Xiaoqun, 02

Wei, Zhi, OM, OP, OT, OU

Wu, Chun-ting, 0W, 12

Wu, Kaifeng, OB

Wu, Shuling, 02

Wu, Yuelong, 0H

Xiao, Zefeng, 10

Xing, Fei, 0H

Xing, Hualu, 01, 0V

Xing, Zheng, 02

Xu, Bing, 11

Xu, Bo, 05

Xu, Zhaopeng, OR

Xuan, Ting, 0Y

Xue, Chen-yang, 04

Xue, Qingyun, 06

Yan, Zhanjun, 14

Yang, Guang, 0A

Yang, Hua-bin, 09

Yang, Ping, 11

Yang, Yongqiang, 10

Ye, Yunxia, 0Y

You, Zheng, 0H

Yu, F. X., 0F

Yu, Hua-dong, 0M, 0O, 0S

Yu, Jiaxin, 17

Yu, Kai, 12

Yu, Ruitao, 18

Yu, WenPeng, 0X

Yu, Yongji, 0L

Yu, Yong-ji, 0W

Yuan, Boshi, OM, OP, OS, OU

Zang, Hongbin, 17

Zhai, Rui-zhi, OL, OW

Zhang, Haomin, OC

Zhang, Hong-ji, 09

Zhang, Lei, 08

Zhang, Liang, 08

Zhang, Wei, OK, ON, OT

Zhang, Xiaoling, OR

Zhang, Xin, OR

Zhao, EnYi, 11

Zhao, Hua, 05 Zhao, Jianlin, 06

Zhao, Jing, 0W

Zheng, Li, OB

Zheng, Xin, 09

Zhou, Chenghong, 15

Zhou, Houming, 0C

Zhou, Jianzhong, 0D

Zhou, Yingyue, 17

Zhu, Xu-bo, 08

viii

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Introduction

We had the great honor of organizing the International Symposium on Optoelectronic Technology and Application 2014 (IPTA 2014) in Beijing. It was truly a great pleasure for us to greet nearly 1,000 participants from many different countries attending IPTA 2014! We firmly believe that the symposium will become an important international event in the field of photoelectronic technology.

IPTA 2014 was sponsored by Chinese Society of Astronautics (CSA) and China High-tech Industrialization Association, technically co-sponsored by SPIE, and organized by Photoelectronic Technology Committee, Chinese Society of Astronautics. 27 cooperating organizations supported the conference. There were nearly 600 papers accepted for presentation at IPTA 2014, contributed by over 1078 authors from more than 10 countries, including United States, United Kingdom, Germany, France, Norway, Australia, Canada, Japan, Korea, Russia, and China. We had six plenary speeches and 228 well-known scientists and experts, from both home and abroad to give invited talks at different sessions.

The purpose of IPTA 2014 was to provide a forum for the participants to report and review innovative ideas, with up-to-date progress and developments, and discuss the novel approaches to application in the field of photoelectronic technology. We sincerely hope that the research and development in the optical and photoelectronic fields will be promoted, and international cooperation sharing the common interest will be enhanced.

On behalf the Organization Committee of IPTA 2014, we would like to heartily thank our sponsors and cooperating organizations for all they have done for the conference. We would also like to thank the authors for their contribution to the proceedings; the participants and friends of IPTA 2014, for their interest and efforts in helping us to make the symposium possible; and the Program Committee for their effective work and valuable advice, especially the IPTA 2014 Secretariat and the SPIE staff, for their tireless efforts and outstanding services in preparing the conference and publishing the Proceedings.

Guofan Jin Songlin Zhuang IPTA 2014 Symposium Committee Chairs